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 (71)Applicant : FUJITSU LTD
 FUJITSU VLSI LTD

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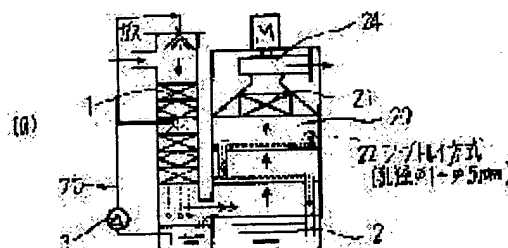
(72)Inventor : KOMATSU KAZUSHIGE

(54) EXHAUST DECONTAMINATION SYSTEM

(57)Abstract:

PURPOSE: To provide the immediate-post treatment exhaust decontamination system which takes advantage of the respective features of a parallel flow wet process decontamination device and a counter current wet process decontamination device, makes up weak point and is compact as the exhaust decontamination system which decontaminates the exhaust discharged from an apparatus for production of semiconductors.

CONSTITUTION: This exhaust decontamination system is constituted by disposing, in series, the parallel flow wet process decontamination device 1 and counter current wet process decontamination device 20, which are respectively used to remove the harmful components included in the exhaust, the former in a front stage and the latter in a rear stage. The above-mentioned system is provided with a washing liquid replenishing port 22 for replenishing a washing liquid in the upper part of the counter current wet process decontamination device 20 and is provided with a washing liquid recovering tank 20 for recovering the washing liquid in the lower part of the counter current wet process decontamination device 20. Further, the system has a function to circulate and supply the washing liquid to the parallel flow wet process decontamination device 1 by a washing liquid circulating pump 3 from the washing liquid recovering tank 2.



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